

9. (Amended) The method of Claim 7, wherein sizes and shapes of said independent spot patterns can be adjusted to control roughness degrees of said pixel electrode.

10. (Amended) The method of Claim 7, wherein sizes and shapes of said independent spot patterns can be adjusted to control roughness degrees of said photosensitive passivation layer.

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11. (Amended) The method of Claim 7, wherein said independent spot patterns are defined by forming hollow areas on said mask.

12. (Amended) The method of Claim 7, wherein said independent sport patterns are defined by forming the covering area on said mask with chromium films.

13. (Amended) The method of Claim 7, wherein a first distance between two adjacent said independent spot patterns is smaller than a resolution of an exposure system while a second distance between adjacent said independent spot pattern and said contact hole pattern is larger than said resolution of said exposure system.--